

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

<b>In re United States Patent Application of:</b>		)	<b>Docket No.:</b>	<b>020732-110.694</b>
<b>Applicant:</b>	<b>KORZENSKI, Michael B., et al.</b>	)	<b>Examiner:</b>	<b>AHMED, Shamim</b>
<b>Application No.:</b>	<b>10/807,858</b>	)	<b>Art Unit:</b>	<b>1792</b>
<b>Date Filed:</b>	<b>March 24, 2004</b>	)	<b>Confirm. No.:</b>	<b>5492</b>
<b>Title:</b>	<b>COMPOSITION USEFUL FOR REMOVAL OF BOTTOM ANTI-REFLECTION COATINGS FROM PATTERNED ION- IMPLANTED PHOTORESIST WAFERS</b>	)	<b>Customer No.:</b>  <b>24239</b>	
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**RESPONSE TO THE OCTOBER 12, 2007 OFFICE ACTION, SUPPLEMENTAL  
INFORMATION DISCLOSURE STATEMENT, DECLARATION UNDER 37 CFR §1.131  
AND REQUEST FOR CONTINUED EXAMINATION IN UNITED STATES PATENT  
APPLICATION NO. 10/807,858**

Mail Stop AF  
Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450

Sir:

This responds to the October 12, 2007 Office Action in the above-identified application.

The claims of the application are set out in the following **Section I (The Claims)**.

Remarks addressing the substance of the October 12, 2007 Office Action are set out in the **Section II (Remarks)** hereof.